







MSFC Tech Days

The COI Semi-Rigid Hybrid Mirror

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Agenda

- Hybrid Design Overview
- Optical Processing
- Modal Correlation
- Cryo Test 1
- Optical Processing
- Cryo Test 2
- Optical Processing
- Cryo Test 3









NMSD Program Requirements

<u>Parameter</u>	<u>Value</u>	<u>Goal</u>
Shape Aperture	Spherical 1.6m	
F/No.	f/6	f/5
No. of Actuators	A/R for figure and/or phasing	
Figure	<λ/4 PTV (visible)	<λ/10 PTV
Mid-Spatial Errors	<λ/10 PTV (visible)	< λ/20 PTV
Mid-Spatial Scale	1 - 10 cm	
Finish	<2 nm RMS	1 nm RMS
Areal Density (PMA)	15kg/m²	<15kg/m²









NMSD Hybrid Design Overview

- Combine Desirable Attributes of Both Glass and Composite
- Structurally Efficient (Bonded) Sandwich Construction
 - Zerodur Facesheet
 - Composite Backplate and Core
 - Low Mass, High Stiffness Support for Zerodur Facesheet
 - Thermal Expansion Match of Zerodur (Ambient to 35K)





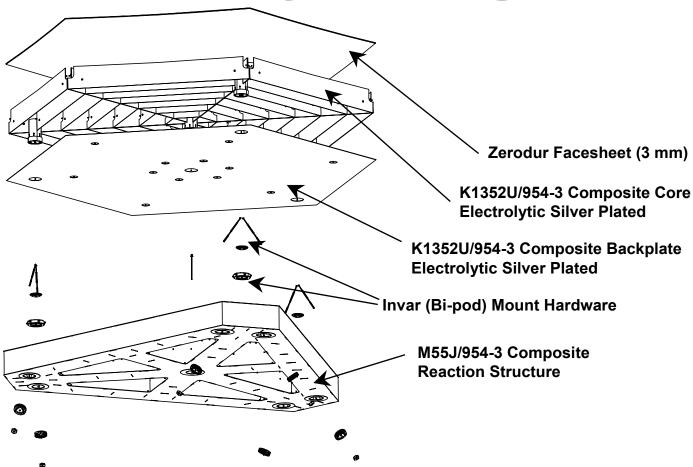








Hybrid Design



- Primary Mirror Assembly Areal Density: 15kg/m²
 - Mirror Substrate: 11kg/m²
 - Reaction Structure and Invar Mounts: 4kg/m²



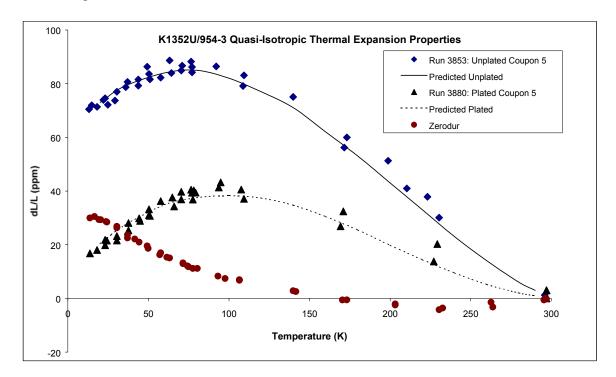






Processing of NMSD Components

- Approach to Thermal Expansion Matching of Composite to Zerodur
 - Lamination and Cure Control to Target dL/L Behavior
 - Plating of Composite Elements to Fine Tune dL/L to Match Glass











Test Objectives

- Objectives for Cryo Test 1 and 2
 - Demonstrate the Modal Characteristics of the PMA, Substrate, and Reaction Structure
 - Provide Basic Optical Performance of the Substrate at 35K in Simulated Zero-g Condition
 - Observe the Basic Behavior of The Hybrid Construction
 - Data Feeds Back into the Analytical Understanding of the System
- Objective for Cryo Test 3
 - Final Optical Demonstration after mid spatial correction









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Optical Fabrication

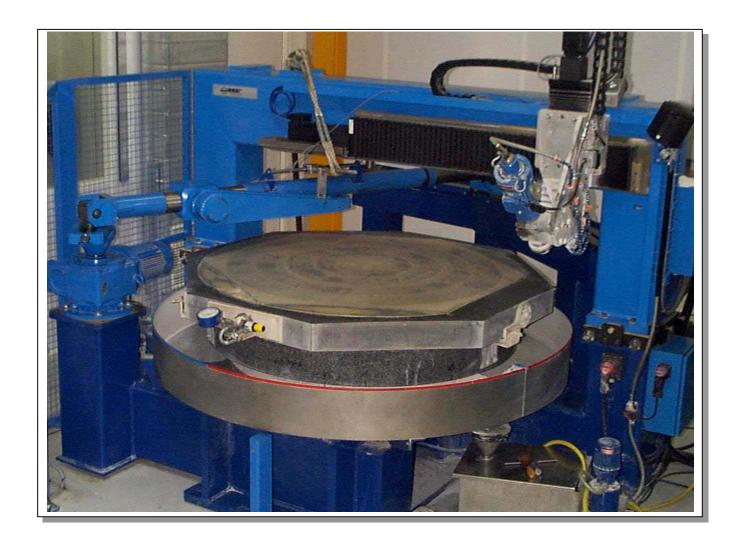








NMSD Mensicus on Granite



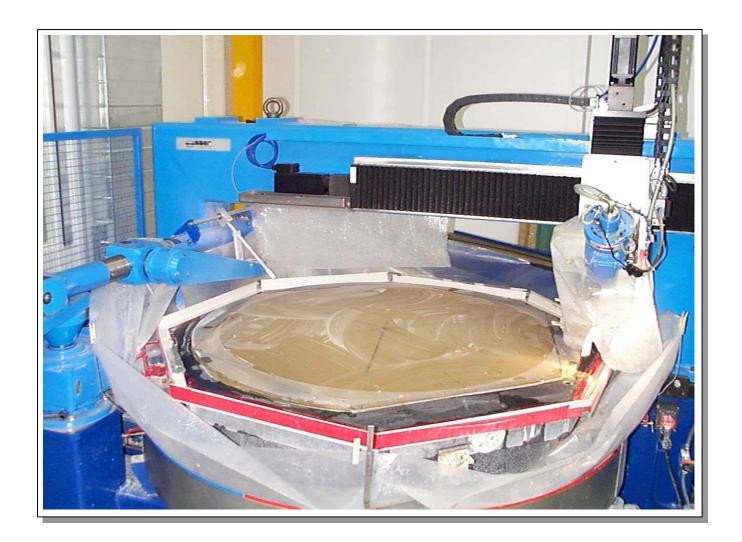








NMSD Meniscus Grinding











NMSD Polishing Strategy

- The Polishing Strategy must be able to:
 - correct for the meniscus distortion induced by the bonding.
 - limit the quilting effect of extremely lightweighted structure.
- The polishing strategy was demonstrated on 300 mm flat subscale risk reduction mirrors
- The selected polishing processes:
 - Low pressure polishing technique
 - Ion Figuring

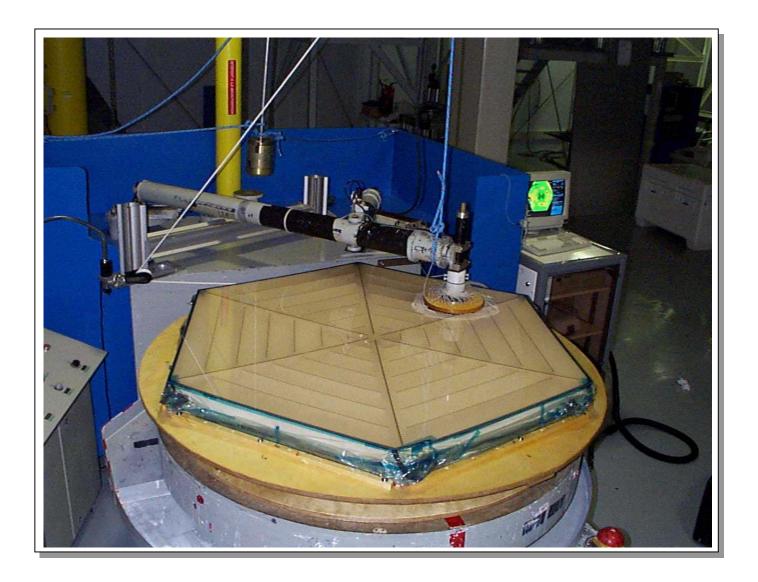








NMSD Mirror Polishing











In-Process Testing Strategy

CMM Measurements:

 High dynamic range, moderate accuracy, used in early stage of polishing.

IR Interferometry:

- High dynamic range, medium range accuracy, used on poor polished surfaces.
- Visible Interferometry:
 - SPSI selected for large dynamic range









CMM Measurements

- Spatial resolution:
 - 100 x 100 points
- Vertical Resolution:
 - 5 µm over 2 x 2 meters
- Estimated Accuracy:
 - 5 μm RMS.
- Measurement Duration:
 - 2 hours











NMSD Composite Pathfinder on Test Stand











IR Interferometry



WaRPP v.2.2 PRO

NMSD_A

Date: 14/04/01

Heure: 10:15:48

Surface d'onde

L = 632.80 nm

Résol. : 200x200

Echelle Lin. :

 $-10.104 \mu m à$

20.788 µm

24520 points

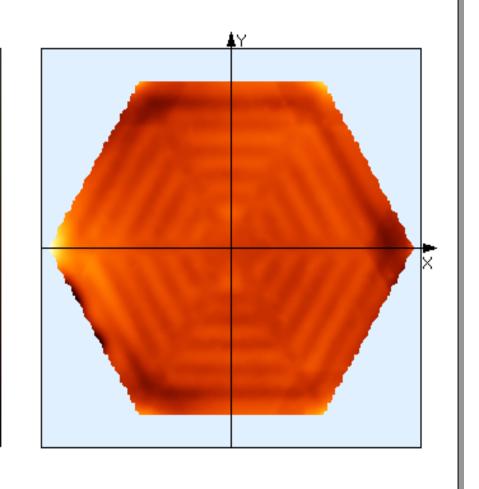
 $Min = -10.104 \mu m$

 $Max = 20.788 \mu m$

Moy = $-0.019 \mu m$

 $P-V = 30.891 \mu m$

 $RMS = 1.905 \mu m$









Surface d'onde (100x100)

06/01/00 14:34:12

-3071

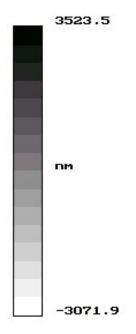


NMSD Predicted Quilting for Initial Optical Processing

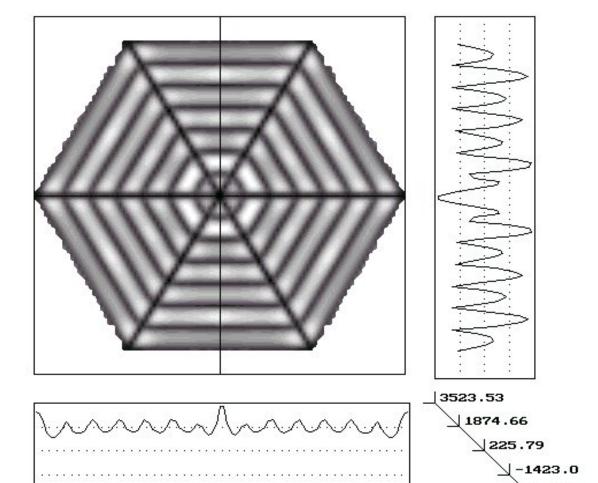


WaRPP V1.68

Min =-3071.9 nm Max = 3523.5 nm P-U = 6595.5 nm Rms = 1421.2 nm



cryo quilting











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Modal Behavior

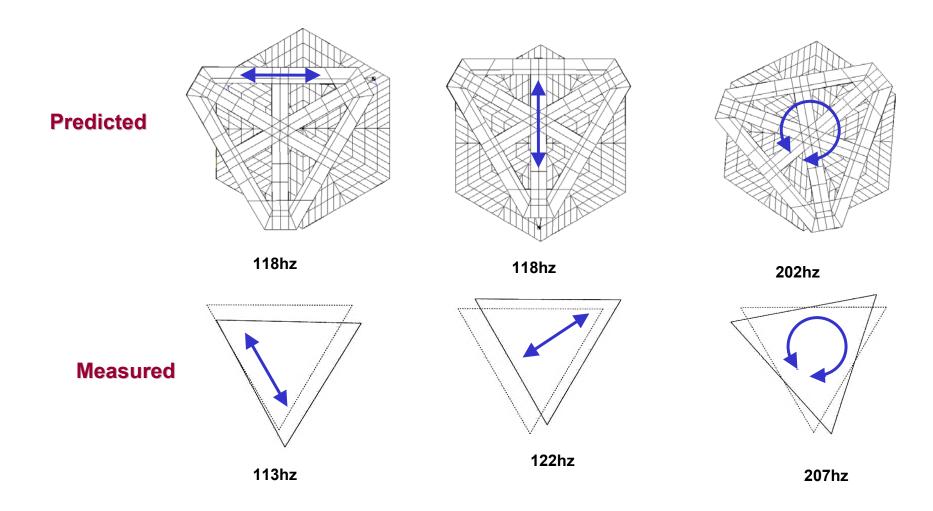








PMA Rigid Body (Bi-Pod) Modes



Agreement Between the Predicted and Measured Rigid Body Behavior

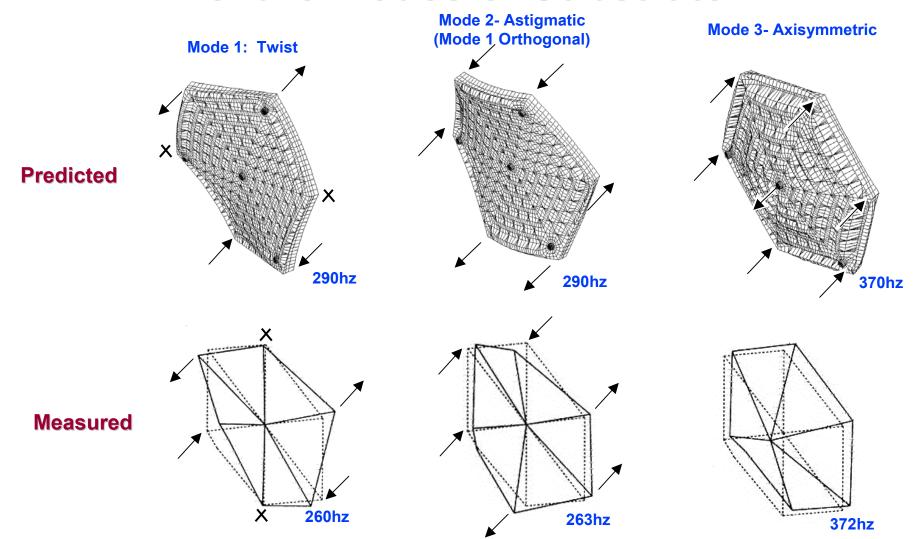








Flexure Modes of Substrate



- Agreement Between Predicted and Measured Bending Behavior of the Substrate
 - Modal Values and Mode Shapes









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Cryogenic Test Overview

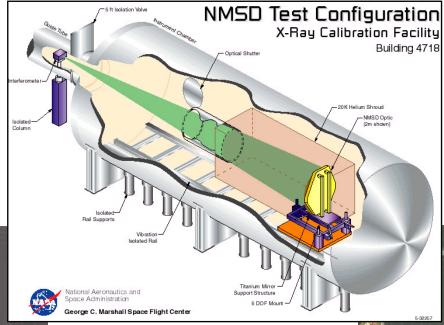


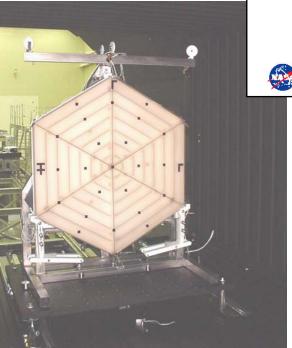


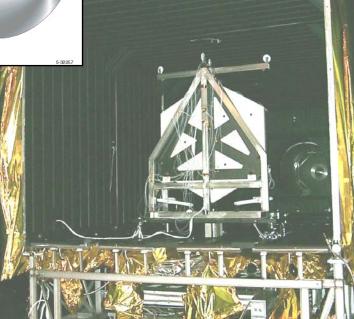




PMA Installation at the XRCF









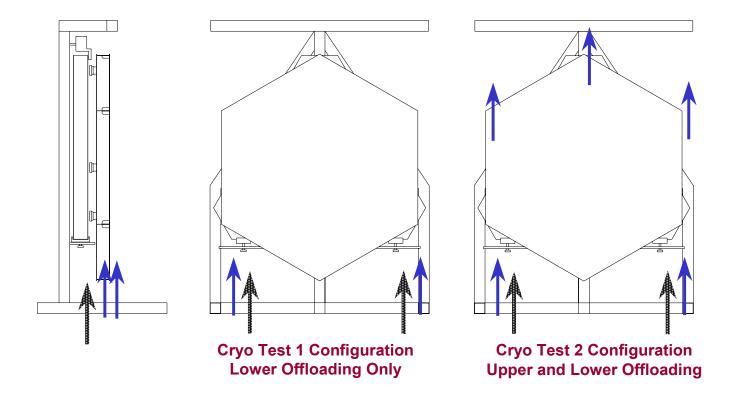






NMSD Gravity Offloading

- Objective
 - Minimize Effects to Mirror Figure from Gravity Induced Deflections
- Approach: Multi-Point Offloading of Mirror Weight
 - Independent Offload of Substrate



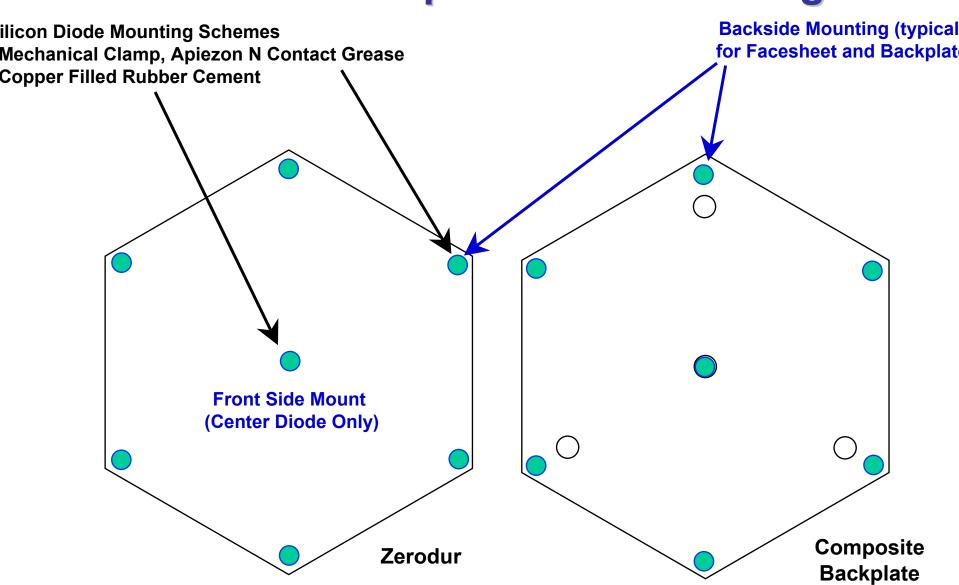








Substrate Temperature Monitoring



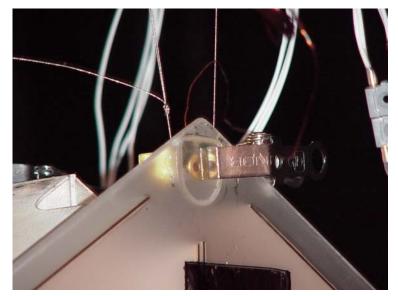


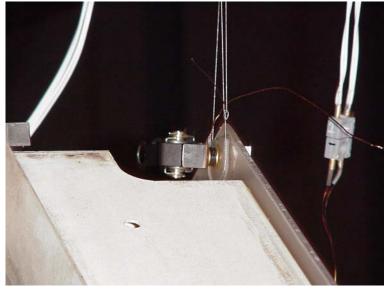






Silicon Diode Mounting















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Temperature Measurements

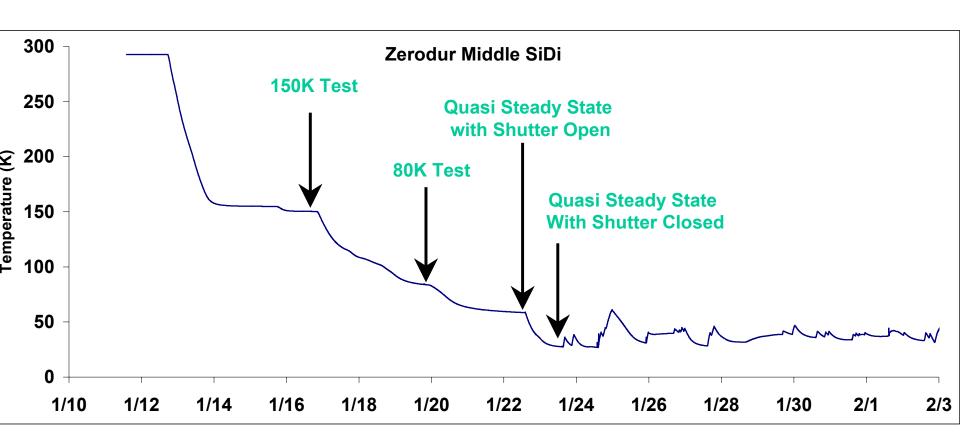








Typical Test Temperatures



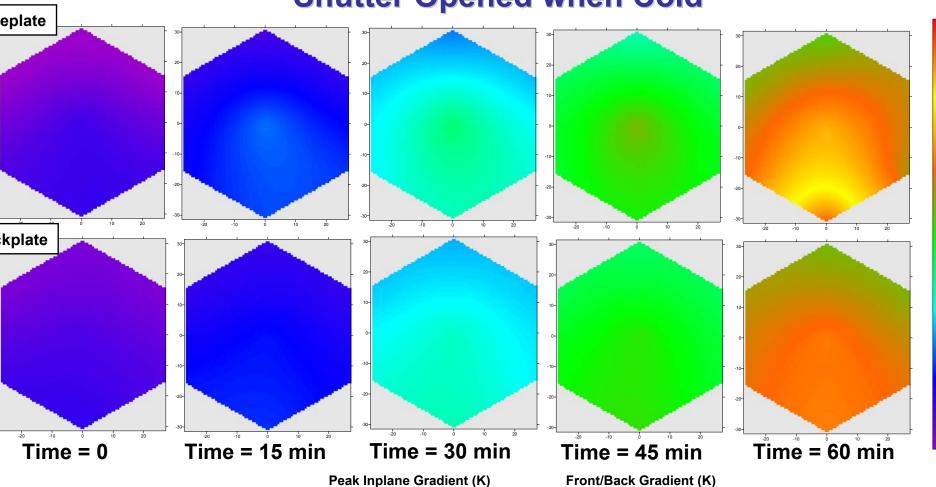








Transient Warm-up Shutter Opened when Cold



Time (min)	Peak Inplane Gradient (K)		Front/Back Gradient (K)		K)
	Faceplate	Backplate	Mid Aperture	Average	Max
0	1.68	1.20	0.20	-0.24	1.10
15	2.05	1.20	0.85	0.15	1.75
30	2.50	1.40	0.80	0.01	2.00
45	2.80	1.40	0.70	-0.11	2.00
60	2.86	1.48	0.73	-0.10	2.21









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Optical Measurements

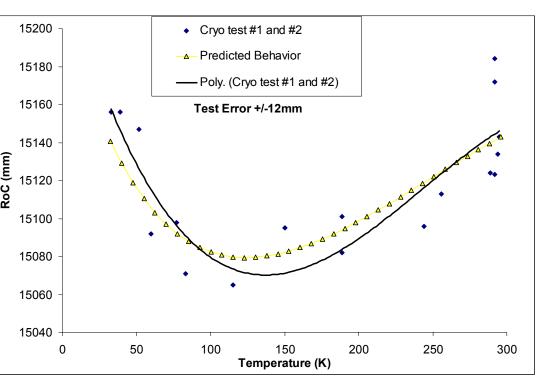


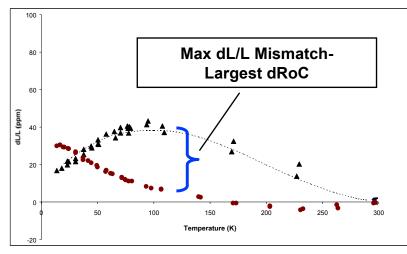






Change in Radius of Curvature





- Bimetallic Behavior (dRoC) of the Substrate Was Derived from the Coupon Level Thermal
 Strain Measurements of the Composite and Zerodur
- Predicted Change in Radius of Curvature is Consistent With Cryo Test 1 and 2
 Measurements









Second Cryo Correction: CMM Results

REOSC SAGEM

WaRPP v.2.2 PRO

nmsdr53d

Date: 09:23:02 Heure: 22/11/00 Surface d'onde

L = 632.80 nm

Résol. : 100x100

Echelle Lin. :

 $-8.063 \mu m à$

14.296 μm

6440 points

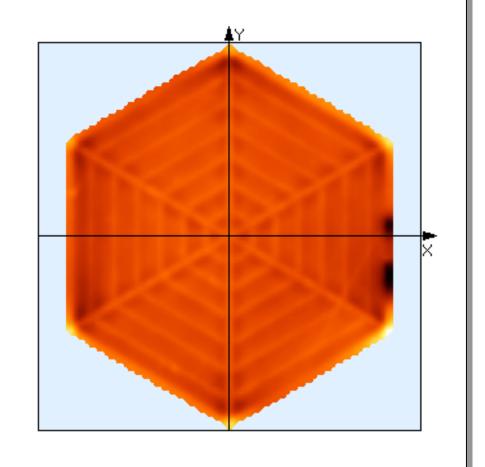
 $Min = -8.063 \mu m$

 $Max = 14.296 \mu m$

Moy = $0.000 \mu m$

 $P-V = 22.359 \mu m$

 $RMS = 1.351 \mu m$











Second Cryo Correction: IR Interferometry



WaRPP v.2.2 PRO

nmsdirr3

Date: 15:19:28

Heure: 23/10/00

Surface d'onde

L = 632.80 nm

Résol.: 100x100

Echelle Lin. :

 $-4.610 \mu m à$

5.583 µm

6452 points

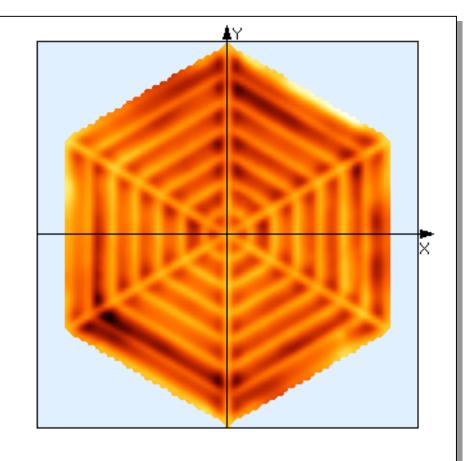
 $Min = -4.610 \mu m$

 $Max = 5.583 \mu m$

Moy = $0.000 \mu m$

 $P-V = 10.193 \mu m$

 $RMS = 1.315 \mu m$











Sub Apertures

REOSC SAGEM

WaRPP v.2.2 PRO

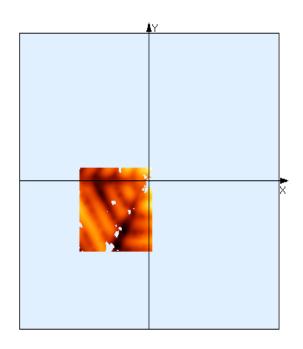
1sub59KT

Date: 29/04/01
Heure: 16:25:26
Surface d'onde
L = 632.80 nm
Résol.: 350x350
Echelle Lin.:
-12.081 µm à
-1.468 µm
9504 points
Min = -12.081 µm
Max = -1.468 µm

Moy = $-8.343 \mu m$

 $P-V = 10.614 \mu m$

RMS = $1.614 \mu m$



REOSC SAGEM



6sub80KT

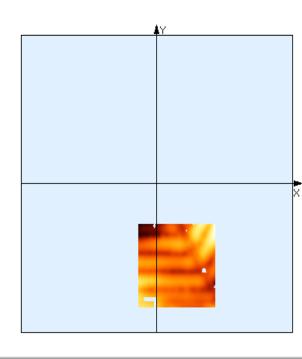
Date: 08/02/01
Heure: 18:04:21
Surface d'onde
L = 632.80 nm
Résol.: 350x350
Echelle Lin.:
-4.505 µm à
5.160 µm
9751 points

Min = $-4.505 \mu m$

 $Max = 5.160 \mu m$ $Moy = 0.050 \mu m$

 $P-V = 9.664 \mu m$

RMS = $1.543 \mu m$











39K Measurement



WaRPP v.2.2 PRO

Sous-pupille

Date: 06/02/01 Heure: 15:57:53

Surface d'onde L = 632.80 nm

Résol. : 350x350

Echelle Lin. :

-9564.332 nm à

7980.905 nm

67848 points

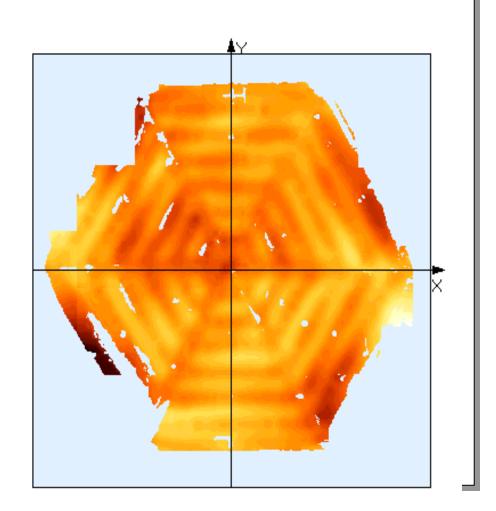
Min = -9564.332 nm

Max = 7980.905 nm

Moy = 54.983 nm

P-V = 17545.237 nm

RMS = 1972.754 nm











60K Measurement



WaRPP v.2.2 PRO

Sous-pupille

Date: 08/02/01 Heure: 16:41:39

Surface d'onde

L = 632.80 nm

Résol. : 350x350

Echelle Lin. :

-6811.968 nm à

7390.163 nm

67795 points

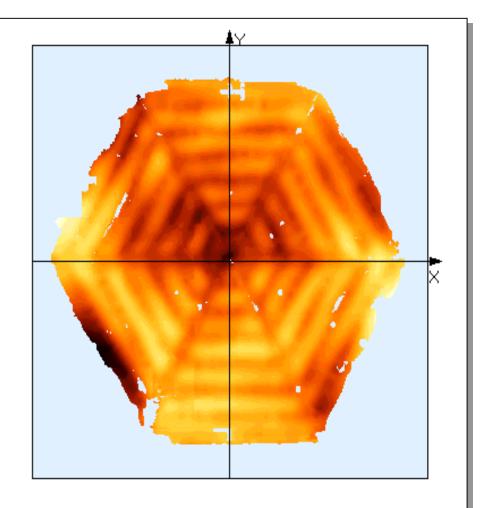
Min = -6811.968 nm

Max = 7390.163 nm

Moy = 231.711 nm

P-V = 14202.131 nm

RMS = 2226.987 nm











Ambient Measurement



WaRPP v.2.2 PRO

Sous-pupille

Date: 13/02/01 Heure: 18:40:24

Surface d'onde L = 632.80 nm

Résol. : 350x350

Echelle Lin. :

-4772.012 nm à

5804.094 nm

73924 points

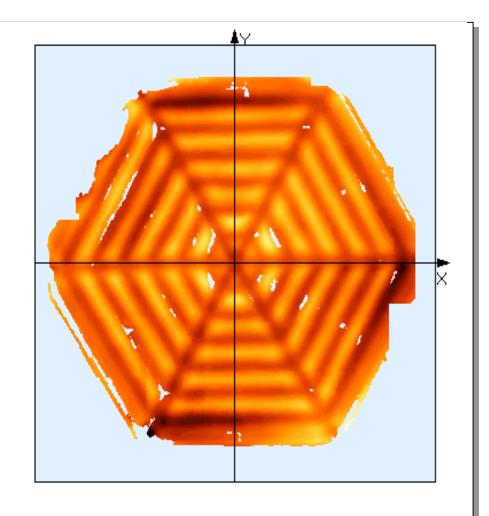
Min = -4772.012 nm

Max = 5804.094 nm

Moy = -66.543 nm

P-V = 10576.106 nm

RMS = 1271.990 nm

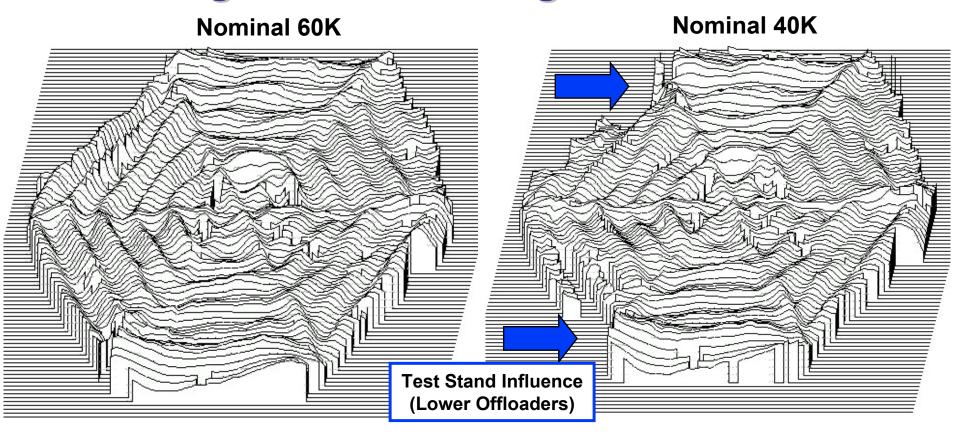








Quilting- Surface Change from Ambient



- Typical Cryo Induced Quilting for the Substrate: 2.5 to 3.0 micron PTV (Average)
- Quilting Behavior is Consistent Between Test 1 and Test 2
- Cryo Quilting is Basically Constant Across the Temperature Range of 40K to 60K
- Cryo Quilting Corrected by Small Tool Polishing and Ion Figuring
 - The Reverse Condition is Cryo-Figured into the Mirror Surface at Ambient Condition









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Ion Figuring









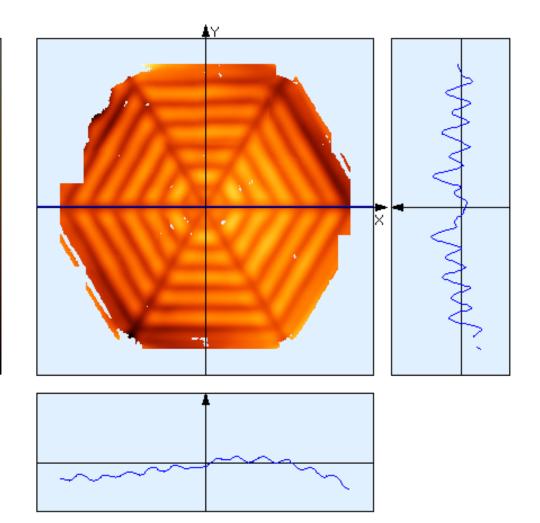
Measurement at Ambient before ion figuring

SAGEM

WaRPP v 2.31 PRO

NMSD 293K

Min = -7084.434 nm Max = 9396.191 nm Moy = -287.566 nm P-V = 16480.625 nm RMS = 1727.978 nm











Expected Map at Ambient after ion figuring



WaRPP v 2.31 PRO

ambient 2

Date: 17/12/01 Heure: 16:23:52

Surface d'onde

L = 632.80 nm

R = 0.000 mm

Résol. : 350x350

Echelle Lin. :

-6992.191 nm à

11720.489 nm

73840 points

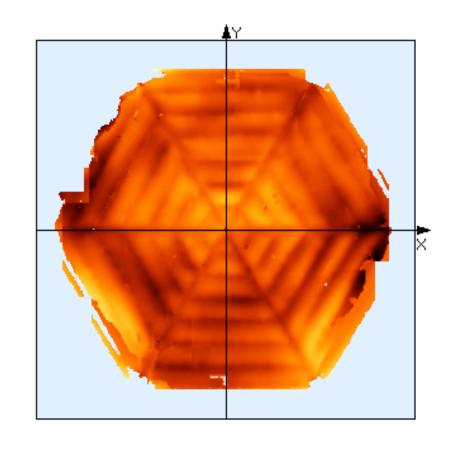
Min = -6992.191 nm

Max = 11720.489 nm

Moy = 0.000 nm

P-V = 18712.680 nm

RMS = 2132.864 nm











Ion figuring runs

Use of a new ion figuring chamber of 2,5 meters capacity.

Three runs have been performed with intermediate WFE measurements and visual inspection between the run.

Special care has been taken to limit the temperature of the mirror face sheet to 60°C

A total of about 500 hours of ion figuring on the mirror.









Measured WFE map after ion figuring



WaRPP v 3.01 PRO

Usion 3

Date: 24/04/02 Heure: 15:45:54

Surface

L = 632.80 nmR = 0.000 mm

Résol. : 350x350 Echelle Lin. :

-7963.842 nm à 10371.839 nm

91289 points

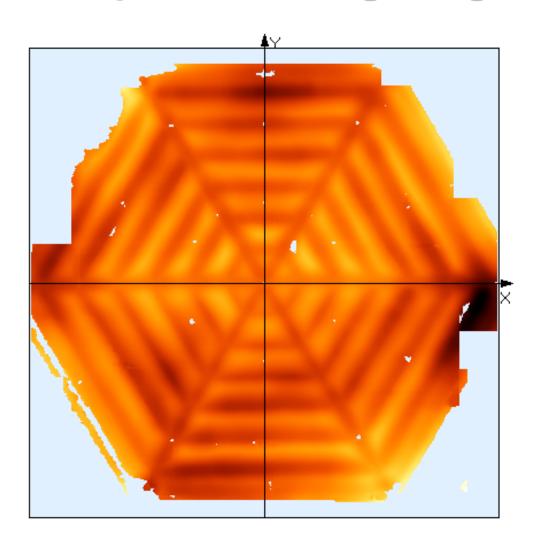
Min = -7963.842 nm

Max = 10371.839 nm

 $M \circ y = -23.372 \text{ nm}$

P-V = 18335.680 nm

RMS = 2001.720 nm









Conclusions

The WFE obtained after ion figuring are close to the expected values:

PTV = 18,3 μm to be compared to PTV=18,7 μm

RMS = 2 μ m to be compared to RMS = 2, 13 μ m

No evolution in the surface micro roughness has been evidenced.









Summary

- Hybrid Technology on Track
- Successful Cryogenic and Structural Demonstrations
 - MinimumTemperature Exposure of 25K;
 - Nominal Test Temperature 40K
 - Figure Repeatability (No Apparent Hysterisis)
 - Agreement Between Test and Analytical Predictions
 - Quilting Analysis Model Updated Based on 2nd Cryo Test
 - Predicted Modal Behavior Consistent with Measurements
- Cryo-Figuring Complete
- Final Cryo Test Awaiting Facility Availability